

L Number	Hits	Search Text	DB	Time stamp
-	458	(wafer or semiconductor or substrate) near25 ((lock or "pass through" or "pass thru" or lock) near25 (vent exhausted or purge or purged or ventilated))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/05/17 00:32
-	761	(wafer or semiconductor or substrate) near25 ((lock or "pass through" or "pass thru" or transfer) near25 (vent exhausted or purge or purged or ventilated))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/05/16 23:06
-	95	((wafer or semiconductor or substrate) near15 (holder or chuck)) same ((lock or "pass through" or "pass thru" or transfer) near25 (vent exhausted or purge or purged or ventilated or blower or fan))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/05/17 00:13
-	174	((wafer or semiconductor or substrate) near15 (holder or chuck)) same ((lock or "pass through" or "pass thru" or transfer) near25 (vent or exhaust or exhausted or purge or purged or ventilated or blower or fan))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/05/17 00:14
-	95	((wafer or semiconductor or substrate) near15 (holder or chuck)) same ((lock or "pass through" or "pass thru" or transfer) near25 (vent exhausted or purge or purged or ventilated or blower or fan))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/05/17 00:13
-	79	((wafer or semiconductor or substrate) near15 (holder or chuck)) same ((lock or "pass through" or "pass thru" or transfer) near25 (vent or exhaust or exhausted or purge or purged or ventilated or blower or fan)) not ((wafer or semiconductor or substrate) near15 (holder or chuck)) same ((lock or "pass through" or "pass thru" or transfer) near25 (vent exhausted or purge or purged or ventilated or blower or fan)))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/05/17 00:14
-	4	((wafer or semiconductor or substrate) near25 ((chuck or holder or support) near15 (pivot or pivoted or traverse or shift))) same ((lock or "pass through" or "pass thru" or lock) near25 (vent exhausted or purge or purged or ventilated))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/05/17 00:34
-	1631	((wafer or semiconductor or substrate) near25 ((chuck or holder or support) near15 (pivot or pivoted or traverse or shift or shifted)))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/05/17 00:36
-	4	((wafer or semiconductor or substrate) near25 ((chuck or holder or support) near15 (pivot or pivoted or traverse or shift or shifted))) same ((lock or "pass through" or "pass thru" or lock) near25 (vent exhausted or purge or purged or ventilated))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/05/17 00:37
-	18	((wafer or semiconductor or substrate) near25 ((chuck or holder or support) near15 (pivot or pivoted or traverse or shift or shifted))) same ((vent exhausted or purge or purged or ventilated))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/05/17 00:37
-	18	((wafer or semiconductor or substrate) near25 ((chuck or holder or support) near15 (pivot or pivoted or traverse or shift or shifted))) same ((vent or exhausted or purge or purged or ventilated))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/05/17 00:37

-	19	((wafer or semiconductor or substrate) near25 ((chuck or holder or support) near15 (pivot or pivoted or traverse or shift or shifted))) same ((vent or exhausted or purge or purged or ventilated or vented))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/05/17 01:00
-	18	"5265632"	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/05/17 01:02
-	648	134/902.ccls. and (vent or vented or exhaust or exhausted or purge or purged or ventilated)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/05/17 01:04
-	144	134/902.ccls. and (vent or vented or exhaust or exhausted or purge or purged or ventilated) same (holder or support or chuck)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/05/17 01:05